Name of the FDP : A One Day Faculty Development

Program on Intellectual Property Rights

Date of the program : 13th April, 2014

RESOURSE PERSON: Prof.Ganapati Panda,

Department of EEE, IIT-Bhubaneswar.

VENUE: AITAM, TEKKALI, 'A' BLOCK SEMEINAR HALL

Convener: Dr. G Sateesh Kumar Professor & H.O.D, Dept of E.C.E



Resource person Interaction with Participants

Aditya Institute of Technology and Management, Tekkali

(An Autonomous Institution)

A One day Faculty Development Program on Intellectual Property Rights.

Department of Electronics and Communication Engineering

13th April, 2014

09.30 a.m to 10:30 a.m Welcome the Dignitaries on to the dais.

Prayer.

Lightning the Lamp.

10:45 a.m to 11:30 a.m Welcome remarks by Dr. G.Sateesh Kumar, HOD &

Convenor

Message by Dr. K.B. Madhu Sahu, Principal,

AITAM

Message by Prof. V.V.Nageswara Rao, Director,

AITAM

Introduction of the Chief Guest: Prof.Ganapati

Panda by Sri T. Viswanadham,

Co-Convener, Asst. Prof, Dept. of E.C.E

Felicitation to the Chief Guest

Brief Message by Prof.Ganapati Panda, Department

of EEE, IIT-Bhubaneswar.

Vote of thanks by Sri. T. Viswanadham,

Co-Convener, Asst. Prof, Dept. of E.C.E.

FDP Report:

Intellectual Property Rights (IPRs) is concerned with the protection of tangible and intangible property. It provides rewards and recognition to inventor/contributor for their research designs, discoveries, inventions, etc. IPR protection plays a key role in gaining modest advantage in terms of technological gains for achieving higher economic growth in a market driven economy.

AIM:

The main aim of workshop is to impart greater awareness about the issue of Intellectual Property Right (IPR), which has gained a special importance for all the domains of socio-economic development. It aid to understand of patentability criteria in details and viable aspect of the patent.

WORKSHOP HIGHLIGHTS:

- 1. Intellectual Property Rights and its protection through patents.
- 2. Basic understanding of the IPR
- 3. Patentability criteria.
- 4. Commercial aspect of the patent